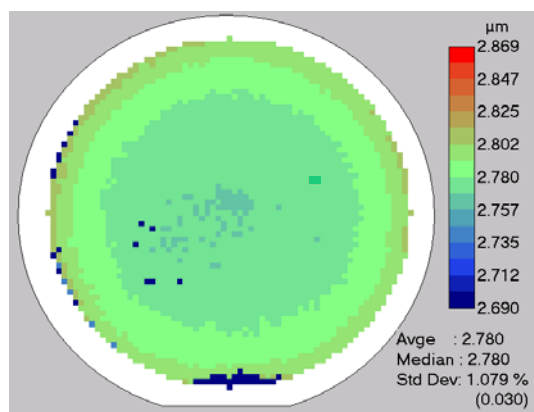


850nm PIN Epiwafer

Part Number: PG1A-1000

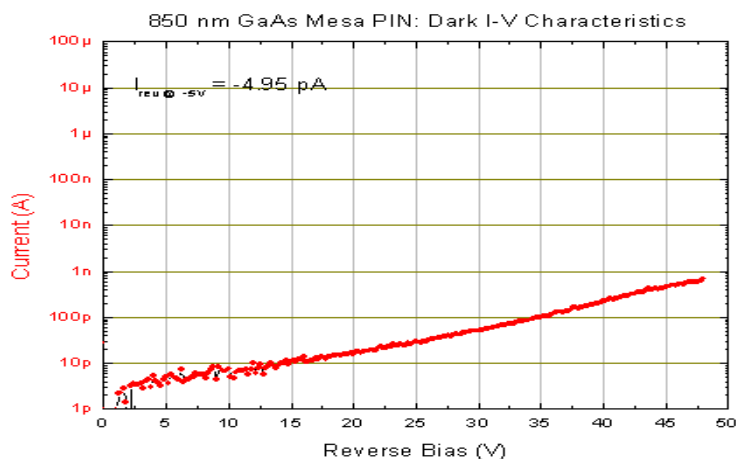
LuxNet's 850nm PIN epi structure was produced using a state-of-the-art MOCVD reactor. We achieved excellent uniformity and reproducibility. Thickness uniformity is better than 1% within a 3" wafer.

Characterization



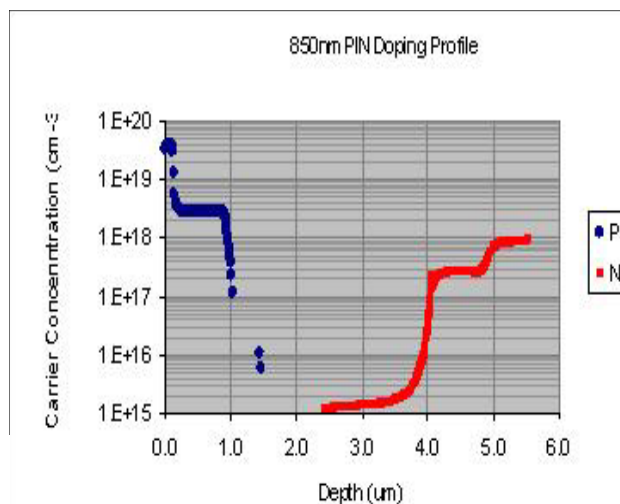
- GaAs absorption layer carrier
- Si & C dopant
- Custom structure available by request

Device Performance



Features

- Excellent thickness uniformity



- Dark Current @ 5V ~2 pA
- Breakdown Voltage > 50V

